Discretely tunable laser based on filtered feedback for telecommunication applications
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Published in:
IEEE Journal of Selected Topics in Quantum Electronics

DOI:
10.1109/JSTQE.2009.2038072

Published: 01/01/2010

Document Version
Publisher's PDF, also known as Version of Record (includes final page, issue and volume numbers)

Please check the document version of this publication:

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Abstract—A novel discretely tunable laser based on filtered feedback is presented. The semiconductor device consists of a Fabry–Perot laser with deeply etched broadband distributed Bragg reflector mirrors. Single-mode operation is achieved by using feedback from an integrated filter. This filter contains an arrayed waveguide grating wavelength router and a semiconductor optical amplifier gate array. Design, simulation, and the first characterization results of this new integrated filtered-feedback tunable laser device are presented. It shows a combination of a simple and robust switching algorithm with good wavelength stability. A rate equation model predicts that a properly designed device can switch within 1 ns. The fast switching and reduced control complexity makes the device very promising for various advanced applications in optical telecommunication networks.

Index Terms—Filtered feedback, packet switching, photonic integrated circuits, semiconductor lasers, tunable lasers.

I. INTRODUCTION

UNABLE lasers are widely used in telecommunication networks nowadays for flexible reconfiguration of the network and in wavelength-division multiplexing (WDM) systems, where a single tunable laser can be used as a replacement for all fixed wavelengths lasers in the network. [1], [2]. Most continuously tunable lasers require complex control electronics to stabilize the laser output signal. A laser based on tunable distributed Bragg reflector (DBR) mirrors, for example, needs accurate current control in at least four sections: the main laser gain section, the front and rear mirrors, and a phase section to prevent unwanted mode-hops. To address a prescribed wavelength, all tuning currents have to be set precisely according to a tuning table. Switching to another wavelength requires a change in the current settings. This will incur slow thermal transients and complex control algorithms are required to keep the wavelength fixed during these transients [3].

The new integrated filtered-feedback tunable laser (IFF-TL) demonstrated in this paper circumvents these drawbacks. Since the device consists of a Fabry–Perot (FP) laser without any tuning elements in the main laser cavity, the device is very stable against temperature fluctuations due to tuning currents. The tuning currents have a very wide tolerance and the control mechanism is therefore much simpler. This potentially reduces the cost of this device compared to conventional tunable lasers.

The principle of the IFF-TL was first described by Docter et al. [4] and then experimentally demonstrated by Matsuo et al. [5]. In this study, two coupled microring filters were used for controlling the wavelength. It was shown that with this approach, the frequency drift due to temperature changes can be reduced from 7 GHz to less than 1 GHz. In another publication by Fürst et al. [6], a ring resonator laser was forced to operate in a single-laser mode by using filtered feedback from a tunable narrow-band DBR grating. In their paper, the authors report a switching speed of 450 ps. However, in both these devices the filter component was controlled by one or two analog input signals, making the operation of the devices still sensitive to temperature fluctuations. In an earlier paper [7], we have shown that semiconductor optical amplifiers (SOAs) can effectively be used as gate switches in discretely tunable lasers. These short gate switches allow for switching times of a few ns in a long extended cavity laser. Incorporating them in a filtered-feedback scheme can significantly reduce the switching speed.

In this paper, we present a laser, which uses a compact arrayed waveguide grating (AWG) integrated with short SOA gate switches for controlling the wavelength. We demonstrate that the filtered-feedback principle in combination with an AWG and an SOA gate switch array allows for simple and stable tuning. To our knowledge the device presented in this paper is the first device that operates in a quasidigital manner, making it a very promising device for large-scale application in fiber networks.

II. OPERATING PRINCIPLE

A schematic picture of the novel IFF-TL is shown in Fig. 1. An FP laser is formed by an SOA and two deeply etched DBR mirrors. The laser cavity length is chosen such that the mode spacing equals the channel spacing in the standard International Telecommunication Union (ITU) grid used for telecom applications [8], e.g., 50 or 100 GHz.

The FP laser is coupled to an AWG filter [9] that splits the light of the FP laser in several waveguide branches. Each branch...
contains an SOA that works as an optical gate. When the SOA is not biased, it will absorb the light, but when put in forward bias, the light will be transmitted or even amplified. The light is then reflected either by a cleaved chip facet, another DBR mirror or any other form of broadband mirror, and fed back through the AWG into the FP laser. The feedback light causes the laser mode with the largest feedback strength to dominate over the other modes and single-mode operation is achieved. The feedback strength is controlled by the gates in the feedback branches. The output light leaves the chip through the opposite DBR mirror.

The concept of filtered-feedback has many advantages over other tunable laser concepts. Compared to tunable DBR lasers [10]–[12], the main difference is that the tuning mechanism is outside the main laser cavity. This means that there is no change in refractive index in the main FP laser cavity while switching the wavelength. Therefore, the wavelength stability is improved and control schemes are simpler. The limitation is that the device can only operate at a fixed set of wavelengths.

The effect of temperature-induced wavelength drift due to changing tuning currents is very small. A good comparison of these temperature effects in a conventional (ring-resonator based) tunable laser and a filtered-feedback tunable laser is given in [5].

Compared to conventional AWG lasers [7], [13], the main advantage of the IFF-TL device is that the AWG is not part of the main laser cavity. Losses caused by the AWG do not have to be compensated by the gain section to reach lasing threshold. Any nonuniformity in the transmission of the AWG channels only translates into a lower feedback signal, which potentially can slow down the switching speeds for these channels, but the threshold current is not changed. Therefore, the carrier density in the laser cavity will be the same, which results in a very stable wavelength.

Theoretically, the device can switch between any two wavelengths without addressing unwanted wavelengths. This prevents the so-called “dark-tuning,” which requires blanking of the laser output while switching the wavelength. However, this was not experimentally confirmed yet.

III. DEVICE DESIGN

A. FP Laser

The layout that was used for the IFF-TL devices is shown in Fig. 2. The main element of the IFF-TL is an 822-µm-long FP laser with 2-period deeply etched DBR mirrors. A detail of the FP laser is shown in Fig. 3. For this device, we use an active–passive integration scheme based on a three-step growth technique as described in [14] and [15]. The waveguides cross the active–passive interface under an angle to reduce any possible reflections from the butt joint. The 2-period DBR mirrors are deeply etched, while the rest of the structure consists of shallow etched waveguides.

The DBR mirrors allow us to control the laser cavity length very accurately. This is important since the mode spacing Δλ is given by the following formula:

$$\Delta \lambda = \frac{\lambda^2}{2N_g L_{cav}}$$

where \(N_g\) is the group index of the waveguide (\(N_g \approx 3.65\)) and \(\lambda\) is the central wavelength (1.55 µm). The cavity length \(L_{cav}\) of 822 µm therefore corresponds to a mode spacing of 0.4 nm or 50 GHz. The exact position of the FP laser modes can be tuned by changing the operating temperature of the laser.

B. AWG Filter

The AWG filter was designed using a deep-shallow double etching technique as described in [16]. The layout of the AWG device is shown in Fig. 4. In this design, the four-channel AWG connected to the FP laser has a channel spacing of 3.2 nm or 400 GHz. This relatively coarse channel spacing keeps the AWG compact. The AWG can be designed so that there is an integer number of FP modes in each AWG channel. This is schematically shown in right part of Fig. 4.

C. SOA Gate Array

In the feedback branches, an array of 100-µm-long SOA gates has been implemented. A detail of the chip layout showing the SOA gate array is given in Fig. 5. Directly after the gates, there are 3-period DBR mirrors that reflect about 85% of the light back through the gates and the AWG to provide the filtered-feedback signal. These DBR mirrors also let a small portion of the light pass that can be used for characterization purposes.

The relatively short SOAs provide only 1 or 2 dB gain when they are biased around 10 mA. However, when the gates are not
biased, virtually all the light is absorbed, effectively creating a large difference in feedback strength between the different wavelengths. The current through the gates can also be used to influence the phase of the feedback signal. This can be used to select the right mode when multiple FP modes are passed through each AWG channel.

D. Deeply Etched DBR Mirrors

The deeply etched DBR mirrors that are used to form the FP laser are schematically shown in Fig. 6. These DBR mirrors provide high reflectivity over the full-gain spectrum [17]. After etching the waveguides and mirrors, the device is planarized with a bisbenzocyclobutene-based polymer (BCB) (refractive index $n_{BCB} = 1.54$). The BCB also penetrates in the gaps of the DBR mirrors. We use a third-order DBR design, where the length of each section equals $(3/4)\lambda/N$ ($N$ is the effective index of the mode in each material). This means that the gaps that are etched in the waveguides are 825 nm wide and the semiconductor left in between the gaps is 360 nm wide. Compared to a first-order design, the third-order design makes it easier to obtain the necessary etch depth.

In the IFF-TL device described in this paper, we used 2-period DBR mirrors to form the FP laser cavity and 3-period DBR mirrors in the feedback branches to reflect the light back to the FP laser. The calculated reflection and transmission spectra of such mirrors are shown in Fig. 7. The 2-period mirror provides about 70% reflectivity, but still allows approximately 20% of the light to pass through the mirror.

IV. FILTERED-FEEDBACK MODEL

In order to demonstrate the operating principle, as well as testing the potential performance of the IFF-TL device, we performed numerical simulations based on an extended Lang–Kobayashi model [18], [19]. This model consists of a set of delay differential equations (DDEs) for the complex slowly varying field amplitudes $E_m$ of each laser mode and the average carrier inversion $\bar{N}$ [normalized at transparency $N_0$] in the FP cavity

$$E_{m} = \frac{1}{2}(1 + i\alpha)\left[\frac{g_{m}(N(t) - N_{0})}{1 + S|E_{m}|^2 + C \sum_{k \neq m}|E_{k}|^2} - \frac{1}{\tau_{m}^{ph}}\right]E_{m} + \gamma_{m}F_{m}$$

$$\dot{F}_{m} = \Lambda E_{m}(t - \tau)e^{i\phi_{m}} + (i\Delta\omega_{m} - \Lambda)F_{m}$$

$$\dot{\bar{N}} = \frac{I}{q} - \frac{N}{\tau_{m}} - g(N - N_{0})$$

where $\tau_{m}^{ph}$ and $g_{m}$ are, respectively, the photon lifetime and the differential gain for mode $m$. For simplicity, we assume equal gain $g = 1.5 \times 10^{-5}$ ns$^{-1}$ for all modes. Different modes in the cavity are coupled nonlinearly by saturation processes such as spectral hole burning that are modeled here by the phenomenological coefficients $S = C = 5 \times 10^{-7}$ and $\alpha = 5$ is the linewidth enhancement factor of the semiconductor material. The injection current is $I = 45$ mA, $q = 1.602 \times 10^{-19}$ is the electron charge and $\tau_{m} = 2$ ns is the carrier lifetime. Spontaneous emission of photons in the laser cavity has been included in the simulation by adding two white-Gaussian noise terms in the field equations.

The feedback is described in (3) in terms of feedback amplitudes $\gamma_{m}$, phases $\phi_{m}$ and delay time $\tau = 2L_{ext}N_{D}/c = 46.2$ ps, where $L_{ext} \approx 1.9$ mm is the length of external branches and $c$ is the speed of light in vacuum. In (3), the change of the group index in the SOA gate sections due to carrier injection is accounted for by the phase $\phi_{m}$.

The AWG in the feedback cavity is modeled as a Lorentzian filter with half width at half maximum $\Delta = 200$ GHz and detuning $\Delta\omega_{m} = 0$, as described by (3), for the auxiliary dynamical variables $F_{m}$. Different values of the bias current on the SOA gates can be modeled with a choice of the feedback strength $\gamma$

$$\gamma = \frac{(1 - R_{DBR})}{\tau_{m}} \sqrt{\frac{P_{ext}^{DBR}}{P_{DBR}} \cdot (1 - A_{DBR})^2 T_{AWG}^2 A_{SOA}^2}$$

where by $R_{DBR}$ we consider the reflectivity of the DBR mirrors of the main cavity. There are also some scattering losses in the DBR mirrors ($R_{DBR} + T_{DBR} < 1$). These losses are
Fig. 8. Dependence of feedback strength $\gamma$ on SOA amplification. Parameters are $\tau_{\text{in}} = 20$ ps, $R_{\text{DBR}}^\text{ext} = 0.85$, $T_{\text{AWG}} = 0.316$.

Fig. 9. Numerical simulations of switching sequence induced by modulation of the feedback parameters. Solid lines: power in mode 1 and mode 2, dashed lines: feedback strength in channel 1 and channel 2. The image on the right shows a detail of the switching dynamics, where the drop in output power is visible when the feedback is switched. Parameters are $\gamma_1 = 0.316$.

The small difference in photon lifetime simulates slightly different propagation losses for the two modes.

accounted for in an absorption term $A_{\text{DBR}}$. For the 2-period DBR mirror, which simulated reflection and transmission spectra, are given in Fig. 7. $A_{\text{DBR}}$ is given by $1 - T_{\text{DBR}}^\text{ext}/(1 - R_{\text{DBR}}) = 1 - 0.2/0.3 = 0.33$. $\tau_{\text{in}} = 2L_{\text{cav}}N_g/c = 20$ ps is the roundtrip time of the main cavity, $R_{\text{DBR}}^\text{ext}$ is the reflectivity of the 3-period DBR mirror at the end of the feedback branches. $T_{\text{AWG}}$ is the transmission of the AWG and $A_{\text{SOA}}$ is the amplification of an SOA. In Fig. 8, we show the dependence of feedback strength $\gamma$ on amplification of the SOA for two different types of DBR mirrors. A lower DBR reflectivity leads to a larger feedback signal, which enhances the switching speed, as will be shown in the next paragraphs.

For the sake of simplicity, we illustrate the result in the simple, but not trivial case of two competing lasing modes of the FP cavity amplified by the feedback from two different AWG channels. Since we assume a flat gain spectrum, the lasing mode is selected by applying the feedback.

We induce mode switching by alternating the feedback parameters $\gamma_1$ and $\gamma_2$ between 0.0 and 6.0 ns$^{-1}$ in a pseudorandom way. Practically, this corresponds to forward biasing one of the SOA gates without biasing the other gates.

Time series of the mode-resolved power from simulations of (2)–(4) are shown in Fig. 9. The device lases in one mode when the corresponding gate is forward biased. When the feedback is moved to another channel, the operation switches to the other mode, because the effective gain of the corresponding mode is increased. The modal power rises and quenches the gain of the other mode. An evidence for this mechanism is shown in the inset of Fig. 9; when the feedback is removed from the lasing mode, its power suddenly drops as a consequence of a change in its effective gain. This mode keeps lasing (although with a lower efficiency) until the other mode—which is now favored by the presence of the feedback—takes over.

The dependence of the switching time on the phase of the feedback is shown in Fig. 10. Here, we assumed that a switch is completed once the mode power reaches 90% of the total power. An average of ten switches is used.

As expected, an increase in the feedback intensity leads to a decrease of the switching time, as it increases the difference between the effective gain of the modes. The order of magnitude of the switching speed is in accordance with the measured switching speed of the ring-resonator based filtered-feedback devices presented in [5] and [6] and the AWG laser using the gate switches described in [7].

The dependence of the switching time on the phase of the feedback is shown in Fig. 11. It is clear that the switching time dramatically increases for feedback phases between $0.5\pi$ and $1.5\pi$, and that no switches are observed for feedback phases around $\pi$, because when the feedback field is out-of-phase with the lasing mode, the effective gain decreases, leading to a further suppression of the side mode instead of a switch.

In the current design, the bias current on the SOA gates can be used to influence the phase of the feedback light, since an increase in carrier density will lead to a change in refractive index. It is therefore possible to adjust the current so that the feedback phase is between 0 and $0.5\pi$ or $1.5\pi$ and 2.0$\pi$. Note that the exact current setting is therefore very tolerant.

V. FABRICATION

The IFF-TL device was fabricated using an active–passive integration scheme developed in cooperation with JDS Uniphase [14], [15]. All layers are grown by metal–organic vapor-phase epitaxy (MOVPE). First, the active layer stack is grown on an n-doped substrate. The active layer is formed by a 120-nm-thick bulk InGaAsP layer (Q1.55, bandgap at $\lambda = 1.55$ $\mu$m) embedded in two 190-nm-thick InGaAsP (Q1.25, bandgap at $\lambda = 1.25$ $\mu$m) confinement layers. The active blocks are then covered by a
lithography-defined SiO$_2$ layer and removed wet-chemically. Then, the passive Q1.25 waveguide layer is selectively grown (500 nm thick) in the second growth step. After removal of the SiO$_2$ mask layer the third and final growth step adds the common cladding and contact layers.

After the growth of the materials, the masking layers for the waveguide definition are applied. First, we deposit a 430-nm-thick SiO$_2$ layer by Plasma-enhanced chemical vapor deposition (PECVD) and then a 50 nm Cr layer is evaporated. The Cr layer allows us to combine the e-beam lithography (EBL) pattern required for the DBR mirrors with the optical lithography pattern required for the waveguides. This combined lithography process is described in [20]. A 320-nm-thick ZEP e-beam resist is applied and the DBR patterns are written using a Raith 150 e-beam system using 30 kV acceleration voltage. The DBR pattern is transferred into the Cr layer by Cl$_2$:O$_2$ inductively coupled plasma (ICP) etching. Then, the waveguide pattern is aligned by optical lithography on the DBR structures. This pattern is also transferred to the Cr layer, which then serves as an etching mask to open the 430-nm-thick SiO$_2$ layer in a CHF$_3$ RIE process.

The device was fabricated using a double-etching technique. This enables the realization of shallow-etched and deeply etched waveguides using the same lithography pattern for the optical channels, avoiding strict alignment requirements. The shallow waveguides are used for low-loss interconnects, the SOAs and some parts of the AWG. The deeply etched waveguides are suitable for tight bends and DBR reflectors. The deep etching was done using a Cl$_2$:Ar:H$_2$ ICP etching process. This process offers straight and smooth sidewalls, which are necessary for the deeply etched DBR mirrors. An SEM image of a fabricated DBR mirror is shown in Fig. 12. The shallow SOA waveguides were later etched by CH$_4$:H$_2$ ICP etching.

After the etching, a 100 nm SiO$_2$ passivation layer is applied by PECVD and the chip is planarized using a single layer of BCB 3022-46. The planarization properties of the BCB are such that when spun at the right speed, hardly any back-etching is required to open the top of all the waveguides. Ti/Pt/Au p-contacts are added using e-beam evaporation and lift off. Then, an extra 1-µm-thick Au layer is electroplated on the large contacts to ensure uniform current injection. Finally, the sample is cleaved and fixed on a copper mount.

Fig. 12. Side-view SEM image of a deeply etched DBR mirror. The SiO$_2$ etching mask is still present. The white lines indicate the position of the contact layer and the waveguide layer (see also Fig. 6).

VI. CHARACTERIZATION

A. LI Characteristics

Fig. 13 shows the $LI$ curves for the IFF-TL device operating at 15 °C. The device has an output waveguide with an angle of 7° with respect to the chip facet. This reduces the reflections from the edge of the chip. The light was collected using a lensed fiber and then split into two branches, one to record the output power and one to record the spectrum. The power collected in the fiber is quite low because of high coupling losses between the chip and the lensed fiber.

The different curves in Fig. 13 were recorded while forward biasing each of the gates separately with 10 mA of current. This provides only about 1–2 dB gain, due to the limited length of the gates. There is also one curve where no gate was opened. From the graphs, it is visible that the threshold current is not affected by the feedback light. This is a first indication that the carrier density in the laser stays constant while switching the channels, which is beneficial for the wavelength stability.

B. Lasing Spectra

Fig. 14 shows the superimposed lasing spectra of the devices when operated at 45 mA. The text near the different laser peaks
indicates which gate was operated. The forward bias on the different gates was between 2 and 13 mA. We can clearly see single-mode operation for each of the channels. The SMSR for the various signals is at least 20 dB. This relatively low value is due to the fact that the passband of the AWG channels is much wider than the 50 GHz modespacing of the FP laser. The difference in transmission of this filter is therefore only small. Moving to a design with more densely spaced channels can improve the side-mode suppression ratio (SMSR).

In Fig. 15(a), smaller part of the spectrum is plotted. In this figure, we observe the subthreshold side modes that originate from the modes of the FP cavity. The mode spacing is 0.404 nm. This corresponds to a frequency spacing of 50.5 GHz, 1% deviation from the ITU spacing. The distance between the lasing channels is 404 GHz.

The plot in Fig. 15 clearly demonstrates the wavelength stability of the device. The FP side modes coincide exactly, no matter which gate is operated. This shows that the group index of the modes in the laser does not change, even though the gates are operated at different currents. This is a clear indication that the carrier density and the temperature in the main laser cavity are very stable, and therefore, we expect very little frequency drift after switching the laser.

It is commonly known that feedback in semiconductor lasers can cause complex dynamic behavior, and can finally lead to coherence-collapse. This is characterized by a large increase in relative intensity noise (RIN), accompanied by an increase in the laser linewidth. However, such regimes require a large feedback delay and/or strength (i.e., large $\tau$ and/or large amplification), which are unlikely in our design (short feedback cavity and short SOA gates). We did not directly address the RIN in our investigation, however, significant increases in the laser linewidth with the feedback were never observed.

In another experiment, the peak wavelengths were recorded using a wavelength meter (ANDO AQ6141). This device records the wavelength and power of the peaks in an arbitrary spectrum. In Fig. 16, the lasing wavelengths are plotted as a function of the forward bias on the different gates, while operating one of the gates at the time. Also, the possible FP-laser modes and the AWG channel passbands are plotted as a reference. The bias current on the main laser cavity was reduced to 41 mA because the lasing wavelength seems to be the least sensitive to fluctuations in the gate currents when operated close to threshold.

Initially, at low gate bias currents, the laser operates at random wavelengths, probably determined by reflections from wavelengths that fall in between two AWG channels. As the bias current is increased the laser becomes single mode. Within the 400 GHz AWG channels, 50 GHz mode-hops are visible. These mode-hops are caused by a change of feedback phase due to the changing gate currents. The wavelength that has the most favorable phase matching will lock the laser. However, the lasing wavelength is usually stable over a wide range in gate currents. This shows that the control of the laser is not very critical and can be realized with relatively simple electronics.

**VII. DISCUSSION**

A novel concept in the field of tunable lasers has been demonstrated. In this section, the most important properties of the IFF-TL will be summarized and put into perspective with respect to the many alternatives that are commercially available nowadays.

**A. Switching Speed**

The theoretical investigation of the filtered-feedback concept shows that nanosecond wavelength switching speeds are possible. Previous experiments with devices operating with a similar feedback concept [5], [6] showed confirmation of the very fast switching speeds that can be obtained using feedback to switch an FP laser. Full dynamic characterization of the current device is still in progress.

The ns switching speed will make the device suitable for packet switching applications. Integrating the tunable laser with a wavelength converter and a passive wavelength router can result in a very fast optical network switch. Furthermore, the device could, in principle, also be integrated with optical header processors, opening the way toward all-optical packet switching.
B. Temperature Effects

Because the SOA gates are placed outside the laser cavity, temperature changes due to the switching currents do not affect the lasing wavelength. This is shown in Fig. 15. The temperature changes of course also influence the phase of the feedback. However, the theoretical investigation in Section IV showed that there is a large operating regime in which small phase changes do not affect the switching speed, and the graphs in Fig. 16 show stable wavelengths over a large range in gate currents. We, therefore, believe that thermal transients due to switching currents will have very little effect on the lasing wavelength.

Wavelength drift due to changes in temperature can be a big problem in tunable lasers using integrated tunable DBR mirrors that are tuned by current injection [21]. A control scheme that precompensates these temperature drifts complicates the control electronics significantly. Matsuo et al. [5] already demonstrated a reduction in optical frequency drift from 7 to 1 GHz in a ring-resonator based IFF-TL device. We believe that the AWG-based IFF-TL can reduce these temperature drifts even further.

C. Control Electronics

Keeping the control electronics simple is important since the cost of the electronics is a major part of the total price of the tunable lasers that are commercially available nowadays. A reduction of these costs would make this device more interesting in high volume, low-cost applications, like metro and access networks.

Existing tunable lasers can address more than 100 WDM channels with only four analog control currents (gain, two tunable DBR mirrors, and a phase control section). However, to find the right combination of current settings requires a complex tuning table and intelligent electronics.

The quasidigital operation scheme of the AWG-based IFF-TL reduces the complexity of the electronics required to control the laser. However, the total number of control currents can become large as the number of wavelength channels increases.

D. Number of Wavelengths

The device presented in this paper has four wavelength channels determined by the AWG. The concept can easily be extended to a larger number of wavelengths, but increasing the density of the AWG channels also results in a larger AWG. The surface of the AWG roughly increases by a factor of 1.5 when the channel spacing is reduced by a factor of 2. With a 50 GHz AWG, the number of wavelengths in the device can be increased to 32.

E. Output Power

The output power of the device in the experiments reported in this paper is relatively low because of the high reflectivity of the front DBR mirror and because the coupling efficiency from the chip to the lensed fiber that was used to collect the light is not very good. The output power of this device can be increased by integrating a booster SOA in the output waveguide. Also changing the laser design so that the output DBR mirror has a lower reflectivity will improve the laser power. The 800 μm cavity should, in principle, allow for at least 10 mW of output power.

F. Conclusion and Outlook

A novel discretely tunable laser based on filtered feedback was presented. A DDE model was developed that allows us to predict switching speeds below 1 ns. We also found that the feedback phase has a large range for which fast switching can be obtained. The predicted dynamical behavior still has to be confirmed with high-speed measurements, but the static characterizations already show that the device has broad operating regimes.

The new concept of the IFF-TL combines high switching speeds with simple wavelength control. While the latter promises a reduction in cost of the control electronics compared to continuously tunable lasers, we believe that the fast switching speed is the biggest advantage of this new device. Together with the fact that the device can be integrated with other active and passive components, we expect that fast switching will enable new applications in packet routing techniques for all-optical telecommunication networks.

REFERENCES


Boudewijn Docter (S’05–M’09) received the M.S. degree in electrical engineering from Twente University, Twente, The Netherlands, in 2002, and the Ph.D. degree from the Eindhoven University of Technology, Eindhoven, The Netherlands, in October 2009.

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During 1974, he was engaged in radar and radar remote sensing. In 1976, he joined the Delft University of Technology, where he was engaged in research on integrated optics with special focus on optical communications in 1981. In 1994, he became a Leader of the Photonic Integrated Circuits Group, Delft University, and was appointed Professor in 1998. In 2002, he moved with his group to the Technical University of Eindhoven, Eindhoven, The Netherlands, where he is currently a Leader of the Opto-Electronic Devices Group, COBRA Research Institute.

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